The Effect of Conditioner Design on Pad Texture

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Phoenix[®] CMP Pad Conditioner





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Phoenix[®] edge CMP Pad Conditioner





Design A

Design B

Design C



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Pad Texture Results



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Phoenix Medium Grit Conditioner- Interferometry



Inner

Middle

Outer

Numerous large asperities,

source of wafer defects.





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Pad Texture (Medium Grit)



Phoenix Fine Grit - Interferometry Line 2



Inner

Middle

Outer



Surface Height (microns)



Pad Texture



Phoenix edge pad Conditioner - Interferometry

2x2 mm image





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Pad Surface Texture Comparison



Interferometry Data



Surface Height (microns)





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Pad Texture Result

for Copper Process



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Experiment Conditions

- Wafer
 - 200-mm blanket copper wafer
- Pad
 - IC1020 M groove
- Slurry
 - 200 ml of Fujimi PL-7103 slurry + 800 ml of Dl H_2O + 33 grams of 30% ultra pure H_2O_2
- Rinse
 - DI H₂O flow rate 2,000 ml/min for 30 seconds.

- Pad Conditioning
 - Morgan Diamond Discs
 - Phoenix Fine grit
 - Phoenix Medium grit
 - Phoenix Coarse grit
 - Phoenix edge Design C (2 runs)
 - In-situ pad conditioning = 6 lb_f
 - Tweaked optimized sweep
 - 2nd Phoenix edge- sinusoidal sweep
- Wafer Polishing
 - Polishing pressure = 2 PSI
 - Platen sliding velocity = 42 RPM
 - Polishing time = 60 seconds



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Composite Topography Images

Phoenix Coarse Grit







Summit Height Distributions





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Asperity Height (Mean & >20um)



Surface Height Probability Density Functions



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Pad Texture and % Asperity Heights >20µ



Summit Sharpness





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Summit Sharpness (Mean & Sharp)



Phoenix Coarse Grit-Image 8



50 µm



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Phoenix Coarse Grit-Image 8 at 2 psi



Contact Area Shape is mostly round

50 µm



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Phoenix Medium Grit-Image 5 at 2 psi



Contact Area shapes are round and elongated

50 µm



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Phoenix Fine Grit-Image 3 at 2 psi



Contact Area shapes are mostly elongated

50 µm



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Phoenix edge- Image 12 at 2 psi



Contact area shapes are elongated and curled

50 µm



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Composite Contact Area Images

Phoenix Coarse Grit



Phoenix Medium Grit



Phoenix Fine Grit



Phoenix edge-Run 1



Phoenix edge-Run 2





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Contact Area Percentage & Point Density



Mean Contact Pressure



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Contact Area Size Distribution



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Contact Area Size (Mean & Large)



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Copper Process Data Results



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Copper Removal Rate & Non-Uniformity



Copper Removal Rate vs. COF



Copper Removal Rate vs. Pad Temperature



Pad Cut Rates



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Summary-Edge Cutting verses Point Cutting

Pad Texture

- Edge cutting produces a smoother pad texture with fewer large asperities
- Edge cutting produces asperity shapes with a sharpness in the mid range of point cutting. However, for point cutting the number of sharp asperities decreases with diamond size.
- Edge cutting produces smaller elongated curled contact area shapes as opposed to larger round contact regions for point cutting.
- Edge cutting produces less contact area, fewer number of contacts, and fewer large contact regions.

Copper Process

- Edge cutting resulted in ~50% increase in copper removal rate over point cutting.
- Edge cutting resulted in comparable non-uniformity
- Edge cutting resulted in vastly reduced pad cut rate over point cutting



Final Thoughts

What causes the increase in copper removal rate?

- COF & pad temperature can not explain the increase in MRR for edge cutting
- Pad surface features and interaction with wafer
 - •No one pad feature shows a direct relationship to MRR.
 - Combination of pad features might explain the increase in MRR
- Slurry flow and mixing due to the geometric design of the spiral conditioner is a strong possibility.

□ Future Work:

- Continue work to find any correlation between Pad texture and MRR
- Investigate the effect of conditioner geometry on MRR
- Marathon study to determine Phoenix edge conditioner life, stability of process, and defectivity



Acknowledgements







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Thank You



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